

Title (en)
METHOD AND DEVICE FOR ADJUSTING VAPOUR PRESSURES WITH HIGH ACCURACY IN THE PRODUCTION OF GAS MIXTURES BY
EVAPORATION OF ONE OR MORE LIQUIDS TO BE EVAPORATED

Title (de)
VERFAHREN UND VORRICHTUNG ZUR HOCHGENAUEN EINSTELLUNG VON DAMPFDRÜCKEN BEI DER HERSTELLUNG VON
GASGEMISCHEN MITTELS VERDUNSTUNG EINER ODER MEHRERER ZU VERDUNSTENDEN FLÜSSIGKEIT

Title (fr)
PROCÉDÉ ET DISPOSITIF POUR LE RÉGLAGE TRÈS PRÉCIS DE PRESSIONS DE VAPEUR LORS DE LA FABRICATION DE MÉLANGES
GAZEUX PAR ÉVAPORATION D'UN OU PLUSIEURS LIQUIDES À ÉVAPORER

Publication
EP 4299154 A1 20240103 (DE)

Application
EP 23182394 A 20230629

Priority
DE 102022116469 A 20220701

IPC 8 full level
B01D 1/00 (2006.01); **B01D 3/34** (2006.01); **B01F 23/00** (2022.01); **B01F 23/10** (2022.01); **C23C 16/448** (2006.01)

CPC (source: EP)
B01D 1/0082 (2013.01); **B01D 3/346** (2013.01); **B01F 23/061** (2022.01); **B01F 23/12** (2022.01); **B01F 33/811** (2022.01); **C23C 16/4481** (2013.01)

Citation (applicant)

- DE 102017102446 A1 20180315 - NETZSCH GERAETEBAU GES MIT BESCHRAENKTER HAFTUNG [DE]
- DE 19858366 B4 20060202 - FRAUNHOFER GES FORSCHUNG [DE]
- US 2021060283 A1 20210304 - LOUWSMA HENDRIK KLAAS [NL], et al
- DE 102013103603 A1 20141016 - OSRAM OPTO SEMICONDUCTORS GMBH [DE]
- DE 4113358 A1 19921029 - SIEMENS AG [DE]
- FINDLEY, M. E.: "Vaporization through Porous Membranes", IND. ENG. CHEM. PROCESS DES. DEV., vol. 6, no. 2, 1967, pages 226 - 230, XP001255205
- WEBB, B. C.: "A Validated Calibration Method for Hydrogen Peroxide Vapour Sensors", RESEARCH ARTICLE IN PDA JOURNAL OF PHARMACEUTICAL SCIENCE AND TECHNOLOGY, vol. 55, no. 1, 2001, pages 49 - 54
- KLEMM, E.; MATHIVANAN, G.; SCHWARZ, T.; SCHIRRMMEISTER, S.: "Evaporation of hydrogen peroxide with a microstructured falling film", CHEMICAL ENGINEERING AND PROCESSING, vol. 50, 2011, pages 1010 - 1016, XP028397177, DOI: 10.1016/j.cep.2011.05.020
- S.L. MANATTM.R.R. MANATT: "On the Analyses of Mixture Vapor Pressure Data: The Hydrogen Peroxide/Water System and Its Excess Thermodynamic Functions", CHEM. EUR. J., vol. 10, 2004, pages 6540 - 6557

Citation (search report)

- [X1] US 2017035985 A1 20170209 - NEWLAND ANTHONY JAMES [NZ], et al
- [X1] US 4582480 A 19860415 - LYNCH BRIAN [US], et al
- [XD1] DE 102013103603 A1 20141016 - OSRAM OPTO SEMICONDUCTORS GMBH [DE]

Designated contracting state (EPC)
AL AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HR HU IE IS IT LI LT LU LV MC ME MK MT NL NO PL PT RO RS SE SI SK SM TR

Designated extension state (EPC)
BA

Designated validation state (EPC)
KH MA MD TN

DOCDB simple family (publication)
EP 4299154 A1 20240103; DE 102022116469 A1 20240104

DOCDB simple family (application)
EP 23182394 A 20230629; DE 102022116469 A 20220701